

ABSTRACT

INTEGRATED CIRCUIT SYSTEM EMPLOYING GATE SHIELD AND/OR GROUND SHIELD

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10 An integrated circuit system that includes: forming a substrate with an active region;
depositing a material over the substrate to act as an etch stop and define a source and a drain;
depositing a first dielectric over the substrate; processing the first dielectric to form features
within the first dielectric including a shield; and depositing fill within the features to
electrically connect the shield to the source of the active region by a single process step

Fig. 5